



SEMIPACK® 2

Fast Diode Modules

SKKE 301F

Features

- CAL (controlled axial lifetime) technology, patent No. DE 43 10 44
- Heat transfer through ceramic isolated metal baseplate
- Very short recovery times
- Very soft recovery over the whole current range
- Low switching losses
- UL recognized, file no. E 63 532

Typical Applications*

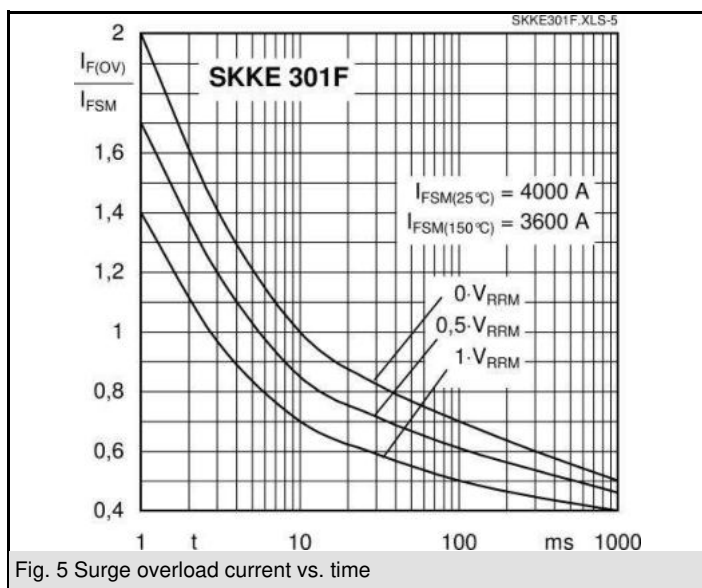
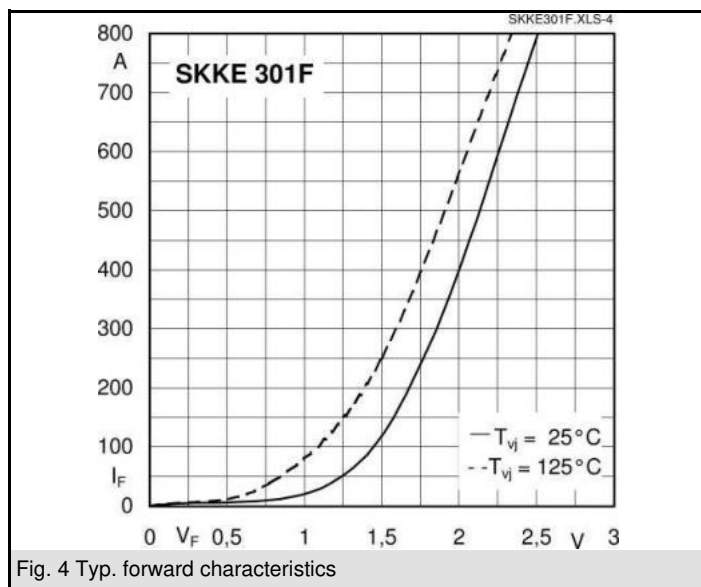
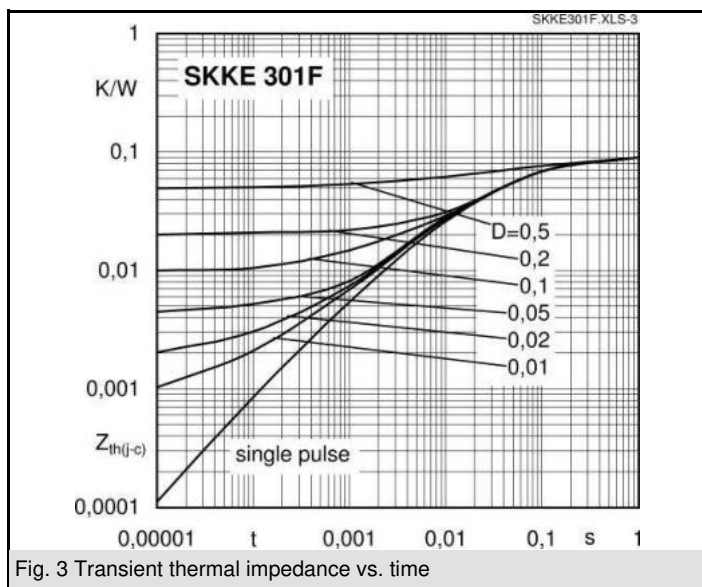
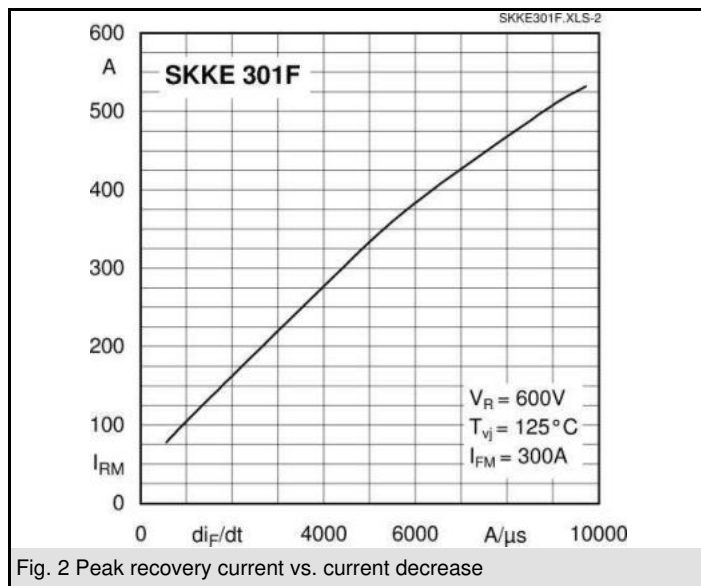
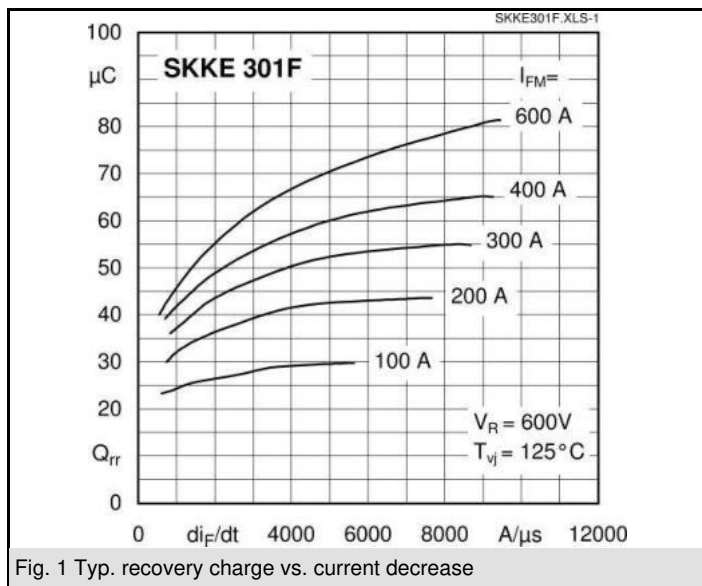
- Self-commutated inverters
- DC choppers
- AC motor speed control
- inductive heating
- Uninterruptible power supplies
- Electronic welders
- General power switching applications

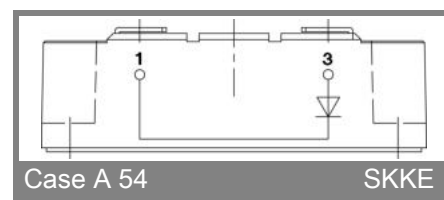
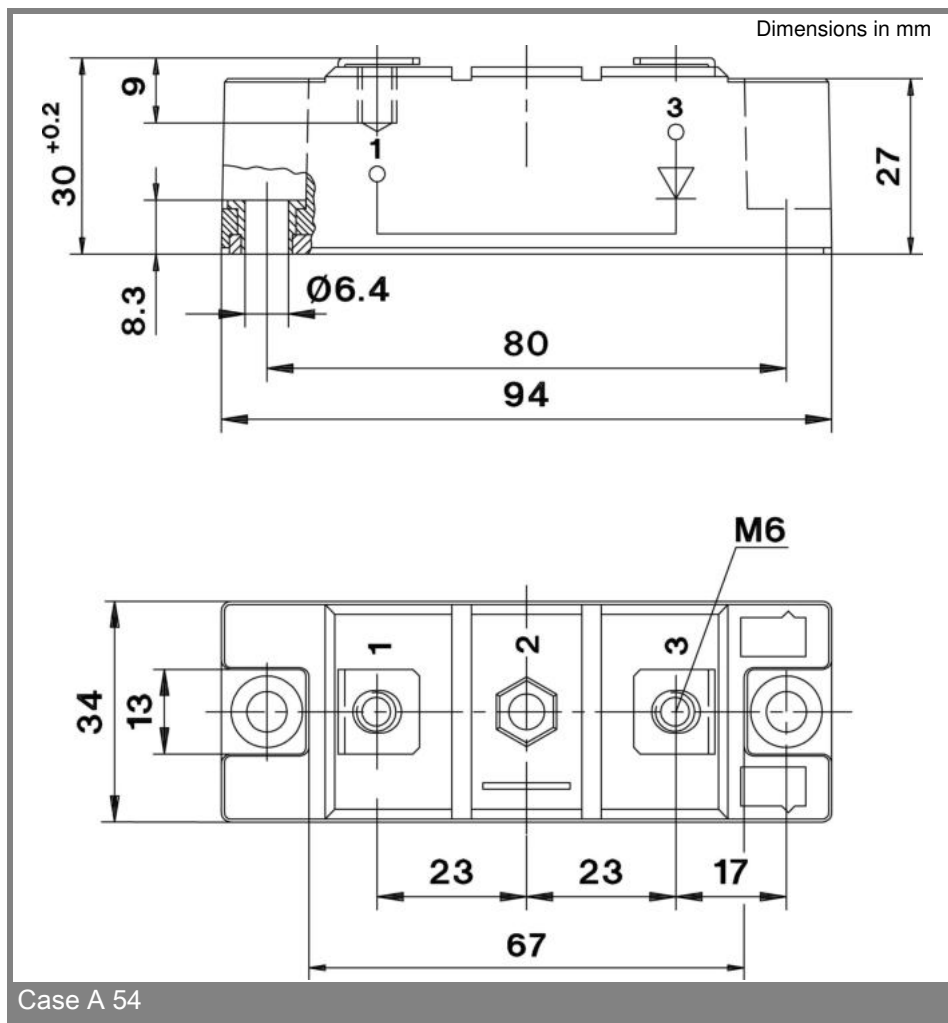
V_{RSM} V	V_{RRM} V	$I_{FRMS} = 450$ A (maximum value for continuous operation) $I_{FAV} = 300$ A (sin. 180; 50 Hz; $T_c = 43$ °C)	
1200	1200	SKKE 301F12	

Symbol	Conditions	Values	Units
I_{FAV}	sin. 180; $T_c = 85$ (100) °C	220 (185)	A
I_{FSM}	$T_{vj} = 25$ °C; 10 ms	4000	A
	$T_{vj} = 150$ °C; 10 ms	3600	A
i^2t	$T_{vj} = 25$ °C; 8,3 ... 10 ms	80000	A²s
	$T_{vj} = 150$ °C; 8,3 ... 10 ms	64800	A²s
V_F	$T_{vj} = 25$ °C; $I_F = 300$ A	max. 2,2	V
$V_{(TO)}$	$T_{vj} = 150$ °C	max. 1,2	V
r_T	$T_{vj} = 150$ °C	max. 2,75	mΩ
I_{RD}	$T_{vj} = 25$ °C; $V_{RD} = V_{RRM}$	max. 1	mA
I_{RD}	$T_{vj} = 150$ °C; $V_{RD} = V_{RRM}$	max. 80	mA
Q_{rr}	$T_{vj} = 125$ °C, $I_F = 300$ A, -di/dt = 2000 A/μs, $V_R = 600$ V	42	μC
I_{RM}		165	A
t_{rr}		690	ns
E_{rr}		10,8	mJ
$R_{th(j-c)}$		0,11	K/W
$R_{th(c-s)}$		0,05	K/W
T_{vj}		- 40 ... + 150	°C
T_{stg}		- 40 ... + 125	°C
V_{isol}	a. c. 50 Hz; r.m.s.; 1 s / 1 min.	4800 / 4000	V~
M_s	to heatsink	5 ± 15 %	Nm
M_t	to terminal	5 ± 15 %	Nm
a		5 * 9,81	m/s²
m	approx.	160	g
Case		A 54	



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* The specifications of our components may not be considered as an assurance of component characteristics. Components have to be tested for the respective application. Adjustments may be necessary. The use of SEMIKRON products in life support appliances and systems is subject to prior specification and written approval by SEMIKRON. We therefore strongly recommend prior consultation of our personal.